



# Role of thermal activation in the spin-orbit torque switching of antiferromagnets

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## Outline

- 1. Thermal activation in the Néel-order switching of Mn<sub>2</sub>Au
- 2. Néel-order switching in magnetron-sputtered CuMnAs films
- 3. Electrical switching of the Néel order in MnN with the spin Hall effect of Pt
- 4. Ohmic contributions to the electrical read-out





# Thermal activation in the Néel-order switching of Mn<sub>2</sub>Au





# **Electrical observation of the Néel-order switching**







# **Pulses and bursts**



- Long single pulse heats the film
- > Chop the single pulse into N shorter pulses
- $\succ$  Keep the total charge per burst constant, i.e.  $Nj\Delta t = const$ .





# **Electrical switching of Mn<sub>2</sub>Au**



а





# **Thermal activation model - Part I**

Idea: Uncoupled grains, coherent switching.

**Energy:** 

$$E/V_g = K_{4\parallel} \sin^2 2\varphi - L \cdot B_{\text{eff}}/V_{\text{cell}}$$

**Energy barrier:** 

$$E_{\rm B} = \min_{cw,ccw} \left( \max_{[\varphi_i,\varphi_f]} [K_{4\parallel} \sin^2 2\varphi - (\boldsymbol{L} \cdot \boldsymbol{B}_{\rm eff})/V_{\rm cell}] - E(\varphi_i) \right)$$

**Effective field:** 

$$\boldsymbol{B}_{\mathrm{eff}} = (\boldsymbol{j} \times \boldsymbol{z}) \cdot \boldsymbol{\chi}$$

- $K_{4\parallel}$ : anisotropy energy density
  - grain volume

 $V_{g}$ :

χ:

- *V*<sub>cell</sub>: unit cell volume
  - spin-orbit torque efficiency







current density

3

- ∆T(t)

2

time (µs)

1

1.0

0.8

0.6

0.4

0.2

0.0

current density (× 10<sup>12</sup> A/m²)

# **Thermal activation model - Part II**

#### Switching rate (Néel-Arrhenius):

$$\frac{1}{\tau} = f_0 \mathrm{e}^{-\frac{E_\mathrm{B}}{k_\mathrm{B}T}}$$

Switching probability:

$$P_{SW}(\Delta t) = 1 - e^{-\Delta t/\tau}$$

Film temperature:

attempt rate

 $f_0$ :

 $\Delta t$ :

*T*<sub>0</sub>:

d:

W:

- pulse width
- base temperature
- film thickness
- current channel width
- $\sigma$ : electrical conductivity
- $ho_{\rm S}$ : density of the substrate
- $C_{\rm S}, \kappa_{\rm S}$ : thermal parameters of the substrate

500

400

300

200

100

ΔT(t) (K)

$$T(t,\Delta t) = T_0 + \frac{2whj^2}{\pi\kappa_S\sigma} \left( \operatorname{arcsinh}\left(\frac{2\sqrt{\kappa_S t/\rho_S C_S}}{\alpha w}\right) + \Theta(t-\Delta t) \operatorname{arcsinh}\left(\frac{2\sqrt{\kappa_S (t-\Delta t)/\rho_S C_S}}{\alpha w}\right) \right)$$

C.-Y. You et al., Appl. Phys. Lett. **89**, 222513 (2006).





# **Model parameters and PHE calculation**

*K* = fitting parameter

$$\Delta R_{xy} = A \left\langle \sin 2\varphi \right\rangle$$

 $A \approx 1\Omega$ 

 $V_{\rm g} = \frac{\pi D^2}{4}h, D = 22$ nm, d = 25nm

$$V_{\rm cell} = 4.75 \times 10^{-29} {\rm m}^3$$

 $|\boldsymbol{L}| = 2 \times 4\mu_{\rm B}$ 

$$\chi = 0.2 \text{mT} / (10^{11} \text{A/m}^2)$$
  
 $f_0 = 10^{12} \text{s}^{-1}$   
 $w \approx 12 \text{um}$ 

 $\sigma = (73\mu\Omega \text{cm})^{-1}$ 









#### **Experiment vs. theory**



Anisotropy energy per grain:  $K_{4\parallel}V_g \approx 1.5 \mathrm{eV}$ 

Anisotropy energy density:  $K_{4\parallel}V_g \approx 7.5 \,\mu \text{eV/f.u.}$ 

Thermal stability factor at RT:  $_{KV_{T}}$ 

$$\Delta = \frac{\kappa v_{\rm g}}{k_{\rm B}T} \approx 60$$





# Néel-order switching in magnetron-sputtered CuMnAs films





## Magnetron-sputtered CuMnAs



- Growth of CuMnAs from alloy target
- Substrate temperature: 410°C

#### GaAs (001) / CuMnAs 100 nm / Ti 3nm

- Oriented growth of tetragonal CuMnAs with preferred (001) direction
- Perpendicular grain size  $\approx 10$ nm
- Large surface roughness



T. Matalla-Wagner, MM, et al., arXiv:1903.12387





## **Electrical switching of CuMnAs**



T. Matalla-Wagner, MM, et al., arXiv:1903.12387





#### **Parameter extraction**







# Dependences on $T, j, \Delta t$



$$\ln R_e = k_1 + \frac{k_2}{T}$$
$$\ln R_e = m_1 j + m_2 + \ln j$$





We switch grains with lower barrier at lower temperature, because  $\chi$  is constant!

T. Matalla-Wagner, MM, et al., arXiv:1903.12387





# Size matters: grain size distribution and (un-)blocking



"active part" of the distribution, changes with  $T_0$ 

Joule heating makes blocked grains switchable! The switching must be thermally assisted! Otherwise, long-term retention of written state is impossible.





# Electrical switching of the Néel order in MnN with the spin Hall effect of Pt



d



# Switching antiferromagnets with the spin Hall effect



Pulse number





# The antiferromagnet MnN



Ta 10 / MnN 32 / CoFe 1.6 / Ta 2





# **Electrical switching of MnN**





M. Dunz, T. Matalla-Wagner, M. Meinert, arXiv:1907.02386

b)





#### **Electrical switching of MnN: Parameters**









# **Grain size analysis**



Anisotropy analysis via "York protocol":



 $\langle E_B \rangle \approx 0.5 \mathrm{eV}$ @ 9nm

Energy barrier from switching and relaxation:





J. Sinclair et al., J. Magn. Magn. Mater. **476**, 278 (2019) M. Dunz, T. Matalla-Wagner, M. Meinert, arXiv:1907.02386





# **Ohmic contributions to the electrical read-out**

UNPUBLISHED





Former Members

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